

PTO  
APR 02 2003  
PATENT & TRADEMARK OFFICE

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

2862  
#3  
DO  
253  
RECEIVED  
APR - 3 2003  
TECHNOLOGY CENTER 2809

Application of: Han et al.

Attorney Docket No.: KLA1P058

Application No.: 10/058,614

Examiner: Not yet assigned

Filed: January 28, 2002

Group: 2862

Title: MULTIPLE ELECTRON BEAM  
INSPECTION SYSTEM USING UNIFORM  
FOCUS AND DEFLECTION FIELD

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail to: Commissioner for Patents, Washington, DC 20231 on March 28, 2002.

Signed:

Mia Mitchell-Haynes

INFORMATION DISCLOSURE STATEMENT  
37 CFR §§1.56 AND 1.97(b)

Commissioner for Patents  
Washington, DC 20231

Dear Sir:

The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure Statement. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. KLA1P058).

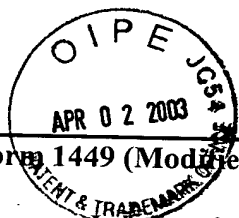
Respectfully submitted,

BEYER WEAVER & THOMAS, LLP

Russell N. Swerdon

Registration No. 36,943

P.O. Box 778  
Berkeley, CA 94704-0778



<b>Form 1449 (Modified)</b> <b>Information Disclosure</b> <b>Statement By Applicant</b> (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	KLA1P058	10/058,614
	Applicant:	
	Han et al.	
	Filing Date	Group
	1/28/02	2862

#### U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date

#### Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No

#### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	A1	T. P. Chang et al., "Arrayed miniature electron beam columns for high throughput sub-100 nm lithography", J. Vac. Sci. Technol. B, Vol. 10, No. 6, Nov./Dec. 1992, pp. 2743-2747.
	A2	E. Yin et al., "Electron optical column for a multicolumn, multibeam direct-write electron beam lithography system", J. Vac. Sci. Technol. B, Vol. 18, No. 6, Nov./Dec. 2000, pp.3126-3131.
	A3	T. R. Groves et al., "Distributed, multiple variable shaped electron beam column for high throughput maskless lithography", J. Vac. Sci. Technol. B, Vol. 16, No. 6, Nov./Dec. 1998, pp. 3168-3173.
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.